THE WAR I STORY FORM PTO-1449 Docket Number (Optional) Application Number 823.0052USQ1 09/836,449 Applicant INFORMATION DISCE IN AN APPLICATION Fonash et al. Filing Date Group Art Unit (Use several sheets if necessary) April 17, 2001 1<del>77</del>5 U. S. PATENT DOCUMENTS **EXAMINER** FILING DATE IF DOCUMENT NUMBER DATE NAME CLASS SUBCLASS APPROPRIATE INITIAL 9/11/01 | Siuzdak et al. 6,288,390 250 288 FOREIGN PATENT DOCUMENTS Translation DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS YES NO OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.) Kim et al. "Thin-Film Micromirror Array." Information Display 4 & 5/99, 30-33. Yonehara et al. "ELTRAN; SOI-Epi Wafer by Epitaxial Layer Transfer from Pouous Si." ELTRAN Business Center, Canon, Inc., Abstract No. 438. Stern et al. "Nanochannel fabrication for chemical sensors." J. Vac. Sci. Technol. 15(6), Nov/Dec 1997, 2887-2891. Turner et al. "Monolithic Fabrication of Nanofluidic Artificial Gel Media for DNA Electrophoresis." SPIE Vol. 3258, 114-121. French. "Development of surface micromachining techniques compatible with on-chip electronics." J. Micromech. Microeng. (1996) 197-211. Sugiyama et al. "Micromachined sensors using polysilicon sacrificial layer etching technology." IEDM Tech. Dig., (1994) 127-130. Bell et al. "Porous silicon as a sacrificial material." J. Micromech. Microeng. 6 (1996) 361-369. Steiner et al. "Using porous silicon as a sacrificial layer." J. Micromech. Microeng. 3 (1993) 32-36. Boer et al. "Micromachining of buried micro channels in silicon." J. Micromech. Systems, Vol. 9, No. 1, March 2000, 94-103. Uhlir, Jr. "Electrolytic shaping of Germanium and Silicon." The Bell System Technical Journal. March 1956. 333-347.

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